

# Lithography Roadmap

- All data is actuals except 7nm for GF, Intel and Samsung and 5nm for all.
- Pitch limits:
  - Single exposure – 80nm
  - SADP – 40nm
  - SAQP – 20nm
  - EUV – 2D pattern – 36nm
  - EUV – 1D pattern – 26nm
- Assume FEOL with be SAxP.

